

MedeA Deposition

Atomistic-Scale Simulations of Deposition, Growth, Oxidation, and Etching at your Fingertips

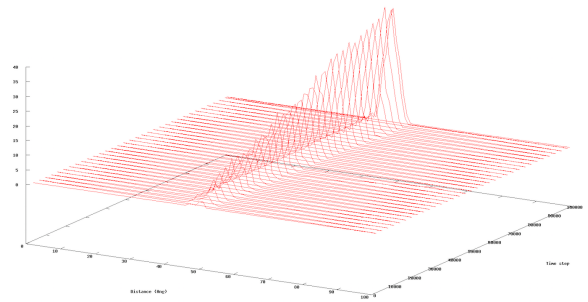
At-a-Glance

Interactions between particles and surfaces control many important processes including deposition, including Micro-cold spray, or oxidation, growth, surface modification, bombardment, sputtering, and etching. The *MedeA Deposition* module facilitates the simulations of automated, continuous impact of pre-defined particles on to a surface and enables you to examine the dynamical processes and mechanisms that govern particle-surface reactions and interactions.

Key Benefits

- Deposition of any amount of various particle types such as atoms, cluster, and molecules
- Impact the surface with user-defined particle velocities or energies, angles, and frequencies
- Study the effects of deposition parameters on surface morphology and atomic distribution
- Automated analysis of results such as particle distribution plots

- *MedeA Deposition* uses the LAMMPS classical molecular dynamics engine for efficient performance on computers from scalar workstations to massively parallel supercomputers
- Temperature control of the substrate with the Langevin thermostat
- Creates distribution plots automatically per deposition particle type for analyses of penetration depth, reaction range, growth thickness, etc.



- Works with reactive forcefields such as MLP, ReaxFF, COMB3, Tersoff, and EAM, as well as non-reactive valence forcefields such as PCFF+

Required Modules

- *MedeA Environment*
- *MedeA Deposition*

Recommended Modules

- *MedeA MLP*, *MedeA ReaxFF*, *MedeA COMB3*, and *MedeA EAM*

Find Out More

Contact Materials Design to see how *MedeA Deposition* can be employed in the following tutorials:

- Deposition of O₂ on Si Surface with reactive forcefields

Computational Characteristics

- Users define impact region, impact velocity/energy, impact angle, impact frequency, and total number of deposits per deposition particle type

